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**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Patent Application of

CHO ET AL. Atty. Ref.: 4105-73; Confirmation No. 6675

Appl. No. 10/568,770 TC/A.U. 1765

Filed: February 21, 2006 Examiner: Unknown

For: FERROELECTRIC THIN-FILM PRODUCTION METHOD, VOLTAGE-APPLICATION  
ETCHING APPARATUS, FERROELECTRIC CRYSTAL THIN-FILM SUBSTRATE,  
AND FERROELECTRIC CRYSTAL WAFER

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May 7, 2007

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

**RESPONSE TO NOTICE OF NON-COMPLIANT AMENDMENT**

Responsive to the Notice of Non-Compliant Amendment dated May 2, 2007, attached is a revised set of claims correcting the errors in claim 21 pointed out in the Notice.

An early and favorable action on the merits is awaited.

Respectfully submitted,

NIXON & VANDERHYE P.C.

By: \_\_\_\_\_

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